

## EAST Search History

| Ref # | Hits | Search Query                           | DBs   | Default Operator | Plurals | Time Stamp       |
|-------|------|--|---|------------------|---------|------------------|
| L1    | 6126 | 438/257,258,241,275,689.ccls.          | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2006/02/28 12:15 |
| L2    | 0    | 1 and ((thin film stack) with \$5mask) | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2006/02/28 12:22 |
| L3    | 9    | 1 and (thin film stack)                | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2006/02/28 12:23 |

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| Ref # | Hits   | Search Query   | DBs   | Default Operator | Plurals | Time Stamp       |
|-------|--------|--|---|------------------|---------|------------------|
| S1    | 0      | (thin film stack) same hardmask same ((anti reflective coating) or ARC) same etch\$4 | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/06/13 12:38 |
| S2    | 0      | (thin film stack) same hardmask same ((anti reflective coating) or ARC)              | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/06/13 12:17 |
| S3    | 0      | ((thin film stack) same hardmask) and ((anti reflective coating) or ARC)             | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/06/13 12:22 |
| S4    | 0      | ((thin film stack) same hardmask)  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/06/13 12:18 |
| S5    | 916    | (thin film stack)  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/06/13 12:31 |
| S6    | 7      | (thin film stack) and hardmask   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/06/13 12:19 |
| S7    | 435233 | (anti reflective coating) or ARC   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/06/13 12:33 |
| S8    | 364    | S7 and hardmask  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/06/13 12:23 |
| S9    | 350    | S8 and etch\$4   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/06/13 12:24 |

## EAST Search History

|     |         |  |   |     |    |                  |
|-----|---------|--|---|-----|----|------------------|
| S10 | 345     | S9 and method  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:28 |
| S11 | 111     | S9 and apparatus   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:29 |
| S12 | 34      | (thin film stack) with apparatus   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:32 |
| S13 | 0       | (thin film stack) with apparatus<br>with ARC                                       | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:32 |
| S14 | 23816   | ((anti reflective coating) or ARC)<br>with apparatus                               | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:34 |
| S15 | 127     | ((anti reflective coating) or ARC)<br>with apparatus with (thin film)              | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:36 |
| S16 | 1525985 | semiconductor  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:35 |
| S17 | 28      | S16 and S15  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:35 |
| S18 | 1       | S16 and ((anti reflective coating)<br>with apparatus with (thin film))             | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:37 |
| S19 | 10      | apparatus same hardmask same<br>((anti reflective coating) or ARC)<br>same etch\$4 | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:39 |

## EAST Search History

|     |      |   |   |     |    |                  |
|-----|------|---|---|-----|----|------------------|
| S20 | 0    | apparatus same hardmask same (anti reflective coating) same etch\$4 | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:40 |
| S21 | 34   | apparatus with (thin film stack)                                    | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:41 |
| S22 | 18   | S16 and S21   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:44 |
| S23 | 2424 | S16 and (antireflection coating)                                    | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 12:45 |
| S24 | 55   | S16 and ((antireflection coating) with apparatus)                   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 13:00 |
| S25 | 267  | S16 and ((antireflection coating) with method)                      | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 13:01 |
| S26 | 48   | S16 and ((antireflection coating) with method with etch\$4)         | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 14:59 |
| S27 | 342  | "16" and ((antireflection coating) with method)                     | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 15:05 |
| S28 | 3    | S27 and chalcogenide  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/06/13 15:05 |

## EAST Search History

| Ref # | Hits    | Search Query   | DBs   | Default Operator | Plurals | Time Stamp       |
|-------|---------|--|---|------------------|---------|------------------|
| S1    | 3       | ("4142926").PN.  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/07/26 14:43 |
| S2    | 12667   | semiconductor with lithography                         | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/07/26 14:46 |
| S3    | 24      | S2 and (thin film stack)                               | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/07/26 14:47 |
| S4    | 1543042 | semiconductor  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/11/09 14:28 |
| S5    | 43735   | S4 and lithography                                     | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/07/26 14:46 |
| S6    | 93      | S5 and (thin film stack)                               | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/07/26 14:47 |
| S7    | 0       | S5 and ((thin film stack) with polysilicon with oxide) | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/07/26 14:48 |
| S8    | 0       | S5 and ((thin film stack) same polysilicon same oxide) | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/07/26 14:49 |
| S9    | 10      | S5 and ((thin film stack) and polysilicon and oxide)   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2005/07/26 14:57 |

## EAST Search History

|     |    |   |   |     |    |                  |
|-----|----|---|---|-----|----|------------------|
| S10 | 4  | S9 and ((anti reflectie) or ARC)  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/07/26 14:58 |
| S11 | 4  | S10 and \$5mask   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/07/26 14:58 |
| S12 | 71 | S4 and ((thin film stack) and polysilicon and oxide)  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/07/26 14:57 |
| S13 | 15 | S12 and ((anti reflectie) or ARC) and \$5mask   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/07/26 15:00 |
| S14 | 15 | S13 and etch\$4   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/07/26 14:59 |
| S15 | 4  | S14 and (((anti reflectie) or ARC) with pattern)  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/07/26 16:02 |
| S16 | 0  | S4 and (((anti reflectie) or ARC) with pattern with hardmask) and ((thin film stack) with hardmask) | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/07/26 16:05 |
| S17 | 0  | S4 and (((anti reflectie) or ARC) same pattern same hardmask) and ((thin film stack) with hardmask) | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/07/26 16:06 |
| S18 | 0  | S4 and (((anti reflectie) or ARC) same pattern same hardmask) and ((thin film stack) same hardmask) | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/07/26 16:08 |
| S19 | 0  | S4 and (((anti reflectie) or ARC) same hardmask) and ((thin film stack) same hardmask)              | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2005/07/26 16:07 |

## EAST Search History

|     |         |   |   |     |     |                  |
|-----|---------|---|---|-----|-----|------------------|
| S20 | 160     | S4 and (((anti reflectie) or ARC) same hardmask)                                    | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON  | 2005/07/26 16:07 |
| S21 | 130     | S4 and (((anti reflectie) or ARC) with hardmask)                                    | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON  | 2005/07/26 16:07 |
| S22 | 64      | S4 and (((anti reflectie) or ARC) same pattern same hardmask)                       | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON  | 2005/07/26 16:08 |
| S23 | 0       | S4 and (((anti reflectie) or ARC) same pattern same hardmask) and (thin film stack) | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON  | 2005/07/26 16:09 |
| S24 | 445     | S4 and (thin film stack)  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON  | 2005/07/26 16:11 |
| S25 | 0       | S4 and ((thin film stack) with hardmask)  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON  | 2005/07/26 16:11 |
| S26 | 10      | S4 and ((thin film stack) with \$5mask)   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON  | 2005/11/09 14:28 |
| S27 | 1584605 | semiconductor   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR  | ON  | 2005/11/09 14:28 |
| S28 | 11      | S27 and ((thin film stack) with \$5mask)  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON  | 2005/11/09 14:29 |
| S29 | 2       | ("20050098821").PN.   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR  | OFF | 2005/11/09 14:30 |

## EAST Search History

|     |   |   |   |    |    |                  |
|-----|---|---|---|----|----|------------------|
| S30 | 2 | S29 and hardmask  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/11/09 14:43 |
| S31 | 2 | S29 and hardmask and (ARC (anti<br>adj reflect\$4 adj coating)) | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/11/09 14:45 |



PALM Intranet

Application  
Number

SEARCH

IDS Flag Clearance for Application 10808793

IDS  
Information

| Content | Mailroom Date | Entry<br>Number | IDS<br>Review                       | Reviewer                    |
|---------|---------------|-----------------|-------------------------------------|-----------------------------|
| M844    | 03-24-2004    | 11              | <input checked="" type="checkbox"/> | 07-06-2004 14:43:35 jsmalls |

UPDATE